

**INFORMATION DISCLOSURE STATEMENT**

Applicant : Hirayama et al.

App. No : 10/590,046

Filed : June 15, 2007

For : BASE MATERIAL FOR PATTERN-  
FORMING MATERIAL, POSITIVE  
RESIST COMPOSITION AND  
METHOD OF RESIST PATTERN  
FORMATION

Examiner : Johnson, Connie P.

Art Unit : 1795

Conf. No. 5635

CERTIFICATE OF EFS WEB  
TRANSMISSION

I hereby certify that this correspondence, and any other attachment noted on the automated Acknowledgement Receipt, is being transmitted from within the Pacific Time zone to the Commissioner for Patents via the EFS Web server on:

April 11, 2011

(Date)

/Neil S. Bartfeld/

Neil S. Bartfeld, Ph.D., Reg. No. 39,901

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing three (three) references to be considered by the Examiner. Please place these documents in the application file.

No fees are believed to be due. However, the Commissioner is hereby authorized to charge any additional fees which may be required to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON &amp; BEAR, LLP

Dated: April 11, 2011

By: /Neil S. Bartfeld/  
Neil S. Bartfeld, Ph.D.  
Registration No. 39,901  
Agent of Record  
Customer No. 20,995  
(858) 836-9000